# Status of 3D silicon pixel detectors for the ATLAS Forward Physics experiment (AFP)

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**IFAE Barcelona** 

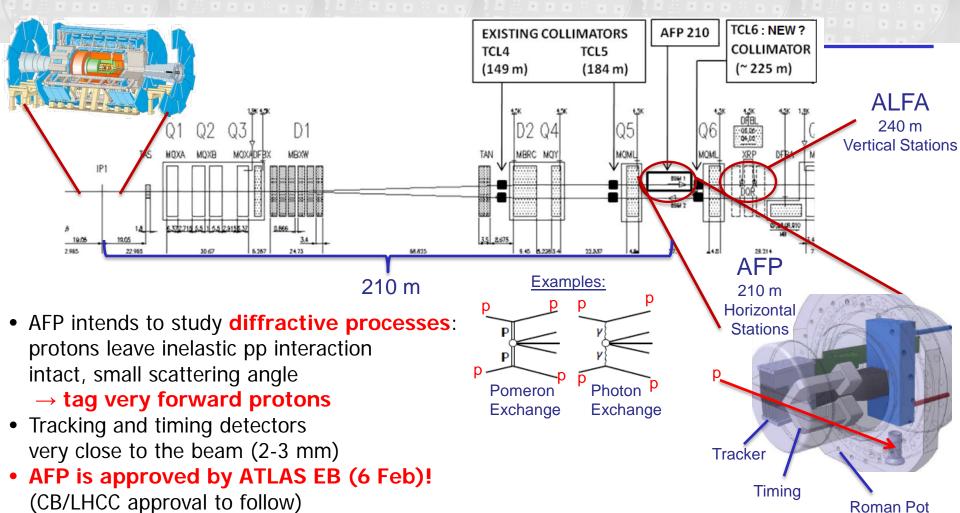
10<sup>th</sup> "Trento" Workshop on Advanced Silicon Radiation Detectors Trento, 18 Feb 2015







#### **AFP Introduction**

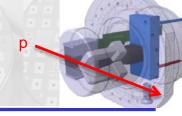


#### 2 stations on each side of IP

- 206 m: tracking only
- 214 m: tracking+timing

- Dedicated short runs at low lumi in initial phase  $(\mu \sim 1)$
- High lumi program (μ~50) under study, revisited later
- Installation in staged approach: first two stations ("0+2")
  - Could aim to install in 2015/16 shutdown!

#### **AFP Detectors**



#### Timing

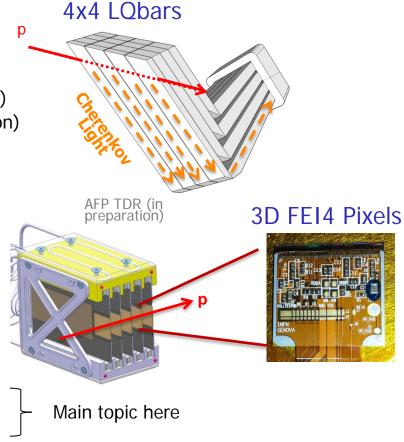
- Task: Constraint on primary vertex for pile-up background rejection
  - $\rightarrow$  10 ps resolution for high- $\mu$  runs (2 mm PV constraint)
  - $\rightarrow$  30 ps for initial low- $\mu$  runs (not needed for 0+2 option)
- Baseline: QUARTIC (Quartz Cherenkov)
- In R&D phase: Si LGAD or Diamond

#### Tracking

- Task: Tag p and measure its momentum (together with LHC magnets)
- Requirements
  - Good position resolution: 10 μm (x), 30 μm (y)
  - Slim edge of side facing beam: 100-200 µm
  - Highly non-uniform irradiation (up to 3x10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup>)

#### Solution

4 layers of slim-edge 3D FE-I4 pixel detectors (telescope configuration)
 → second use of 3D silicon sensors in HEP experiment!

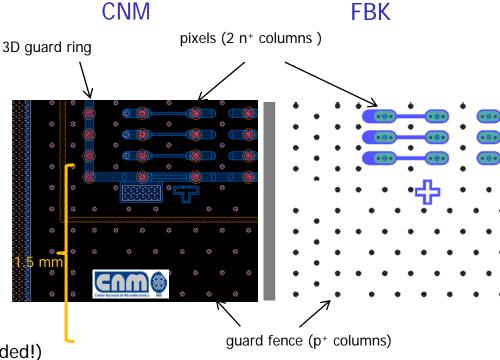


## Sensors and Edge Slimming

FE-I4 3D IBL sensors (CNM and FBK)

(more details in A. Gaudiello's talk at this workshop)

- 336x80 pixels of 50x250 µm²
- p-type bulk, 2 n+ columns per pixel
- Edge termination:
  - CNM: 3D guard ring of n<sup>+</sup> columns
     + p<sup>+</sup> ohmic-column fence
  - FBK: p+ ohmic-column fence
  - Left/right edge: already 200 µm slim edge for IBL
  - Bottom (should be slim for AFP):1.5 mm bias tab in IBL production (not needed!)



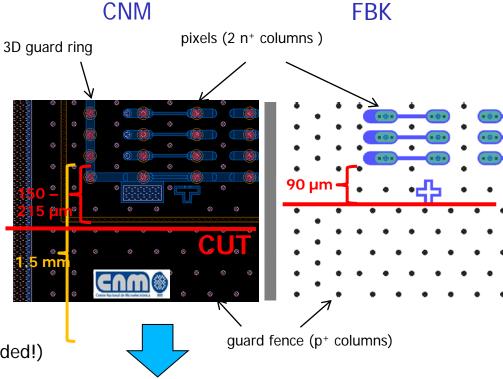
## **Sensors and Edge Slimming**

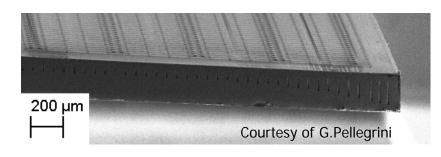
FE-I4 3D IBL sensors (CNM and FBK)

(more details in A. Gaudiello's talk at this workshop)

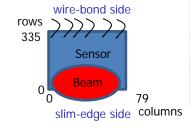
- 336x80 pixels of 50x250 μm<sup>2</sup>
- p-type bulk, 2 n<sup>+</sup> columns per pixel
- Edge termination:
  - CNM: 3D guard ring of n<sup>+</sup> columns + p<sup>+</sup> ohmic-column fence
  - FBK: p+ ohmic-column fence
  - Left/right edge: already 200 µm slim edge for IBL
  - Bottom (should be slim for AFP): 1.5 mm bias tab in IBL production (not needed!)
- Edge slimming of bottom
  - Cut IBL sensors' inactive bottom edge down to 90-210  $\mu m$  (FE-I4 chip: 80  $\mu m$  dead region)
  - Technique here: standard diamond-saw cut

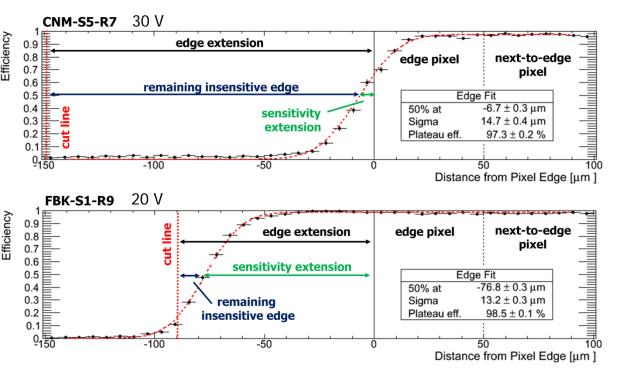
Note: IBL spares used for these studies (not always best quality)





## Slim-Edge Efficiency at Bottom

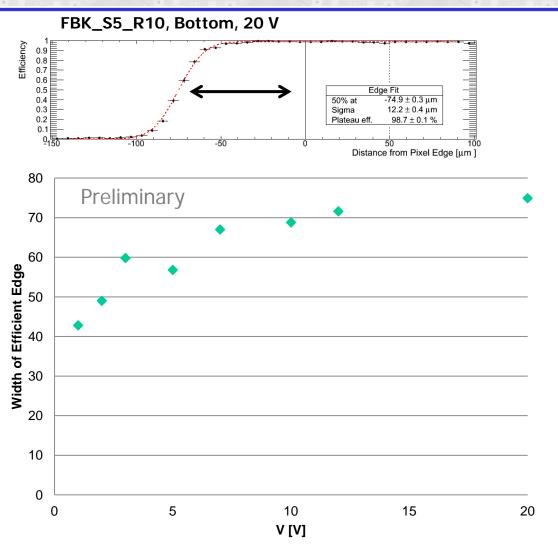


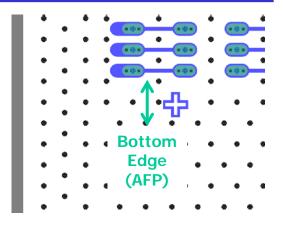


- DESY testbeam (4-5 GeV e<sup>-</sup>) with EUDET-type telescope
- Efficiency stable up to last pixel (smeared by telescope resolution)
- For FBK even ~75 µm beyond:
   Efficient edge due to absence of guard ring
  - $\rightarrow$  <15 µm insensitive edge!
  - → Slimmest edge apart from fully active edge technology
  - But implications on resolution/ alignment if edge pixel is different
- For both CNM and FBK: <150 µm insensitive edge possible</li>
   → AFP slim-edge requirements fulfilled

Sample	FBK-S1-R9	FBK-S2-R10	CNM-S3-R5	CNM-S5-R7
Edge extension after cut	91 μm	$87  \mu \mathrm{m}$	$215  \mu \mathrm{m}$	150 μm
Sensitivity extension beyond last pixel	$77  \mu  \mathrm{m}$	$75  \mu \mathrm{m}$	$1\mu\mathrm{m}$	7 μm
Remaining insensitive edge	$14 \mu\mathrm{m}$	$12  \mu \mathrm{m}$	$214  \mu \mathrm{m}$	143 μm

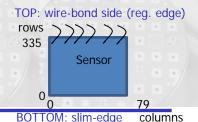
## Development of Edge Extension in FBK Sensor with Voltage



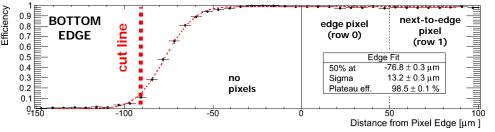


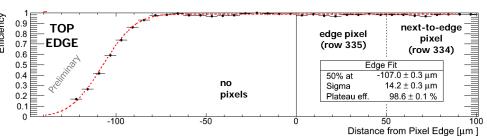
- Width of efficient edge increases with voltage (depletion zone increases)
- Saturation between first and second guard line beyond last pixel

## Edge Extension - Comparison Top-Bottom



FBK\_S1\_R9, 20 V



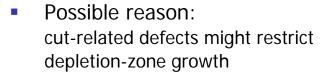


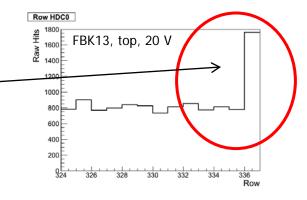
- FBK sensitivity extension at top (107 μm) 30 μm larger than at bottom (77 μm)
  - Although symmetric geometry
  - Top sensitivity extension would surpass cut line (at 90 µm) at bottom!





- $R_{top} > R_{bottom}$  for slim-edge devices (from TB and  $^{90}$ Sr)
- $R_{top} = R_{bottom}$  for regular-edge devices (from  $^{90}$ Sr)





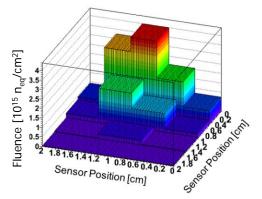
90Sr source scan

		вот	ТОМ	ТОР		
Sensor	or Edge <hit mult=""> R</hit>		R	<hit mult=""></hit>	R	
FBK_S1_R9	Slim bottom	2.05	1.64 ± 0.05	2.04	1.92 ± 0.04	
FBK13	Regular	2.45	2.14 ± 0.08	2.42	2.14 ± 0.07	



#### **Non-Uniform Irradiation**

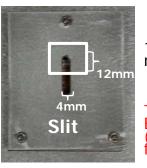
- Highly non-uniform fluence from diffractive p
  - Future high-lumi runs: max. 5x10<sup>15</sup> p/cm<sup>2</sup> (~7 TeV p)
     → focus of studies here
  - Initial low-lumi runs: most of the time retracted to parking position
     → lower and more uniform fluence → less demanding
- 2 irrad. campaigns with different non-uniformity scenarios
  - No 7 TeV irradiation facility available yet
     → Proof-of-principle tests at usual irrad. facilities with lower p energy
  - 1) Focussed 23 GeV p irradiation (CERN-PS)→ fluence spread large, gradual transition



lower p energy
 2) 23 MeV p (KIT) through hole in 5mm Al plate
 → very localised fluence with abrupt transition

~5x10 15 p/cm





# of protons per 100 fb<sup>-1</sup>/ pixel (50µm×250µm)

Beam background not considered!

Sensor area (20 x 20mm)

1.8-3.6 x 10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup>

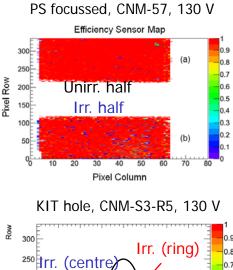
Thanks to Felix Bögelspacher (KIT) for irradiation

To check: Can detectors be operated to give high eff. in all regions?
 (Irrad. side → high V<sub>bias</sub> needed; but unirr. side → low V<sub>BD</sub>)

### **Efficiency Results**

#### **DESY and CERN Testbeams**

Non-Uniform Irradiation	Unirr. Reference	PS Focussed	KIT Hole (circ.)	KIT Hole (slit)		lit)
$\Phi$ [10 <sup>15</sup> n <sub>eq</sub> /cm <sup>2</sup> ]	Unirr.	4.0 (max)	1.8	3.3		3.6
Sample	CNM 55	CNM 57	FBK 12_02_08	CNM S5-R7		CNM S3-R5
Edge	Regular	Regular	Regular	Slimmed		Slimmed
V <sub>bias</sub> [V]	30	130	58	90	100	130
Threshold [ke]	3	1.7	2	2	2	3
ToT @ inj.charge [ke]	10@20	10@20	~11@20	6@10	~5@20	~8@20
SingleSmall Hits Reject	No	No	No	No	Yes	Yes
Eff <sub>max</sub> (unirr) [%]	99	99	98	99	95	94
Eff <sub>max</sub> (irr,centre) [%]	-	98	97	96	94	93
Eff <sub>max</sub> (irr,ring) [%]	-	-	70	93	90	58
	Irradiation  Φ [10 <sup>15</sup> n <sub>eq</sub> /cm <sup>2</sup> ]  Sample  Edge  V <sub>bias</sub> [V]  Threshold [ke]  ToT @ inj.charge [ke]  SingleSmall Hits Reject  Eff <sub>max</sub> (unirr) [%]  Eff <sub>max</sub> (irr,centre) [%]	Irradiation         Reference           Φ [10¹⁵ n <sub>eq</sub> /cm²]         Unirr.           Sample         CNM 55           Edge         Regular           V <sub>bias</sub> [V]         30           Threshold [ke]         3           ToT @ inj.charge [ke]         10@20           SingleSmall Hits Reject         No           Eff <sub>max</sub> (unirr) [%]         99           Eff <sub>max</sub> (irr,centre) [%]         -	Irradiation         Reference         Focussed           Φ [10¹⁵ n <sub>eq</sub> /cm²]         Unirr.         4.0 (max)           Sample         CNM 55         CNM 57           Edge         Regular         Regular           V <sub>bias</sub> [V]         30         130           Threshold [ke]         3         1.7           ToT @ inj.charge [ke]         10@20         10@20           SingleSmall Hits Reject         No         No           Eff <sub>max</sub> (unirr) [%]         99         99           Eff <sub>max</sub> (irr,centre) [%]         -         98	Irradiation         Reference         Focussed         Hole (circ.)           Φ [10¹⁵ n <sub>eq</sub> /cm²]         Unirr.         4.0 (max)         1.8           Sample         CNM 55         CNM 57         FBK 12_02_08           Edge         Regular         Regular         Regular           V <sub>bias</sub> [V]         30         130         58           Threshold [ke]         3         1.7         2           ToT @ inj.charge [ke]         10@20         10@20         ~11@20           SingleSmall Hits Reject         No         No         No           Eff <sub>max</sub> (unirr) [%]         99         99         98           Eff <sub>max</sub> (irr,centre) [%]         -         98         97	Irradiation   Reference   Focussed   Hole (circ.)     Φ [10 <sup>15</sup> n <sub>eq</sub> /cm²]   Unirr.   4.0 (max)   1.8   3.3     Sample   CNM   55   57   12_02_08   S5     Edge   Regular   Regular   Regular   Regular   Slin     V <sub>bias</sub> [V]   30   130   58   90     Threshold [ke]   3   1.7   2   2     ToT @ inj.charge [ke]   10@20   10@20   ~11@20   6@10     SingleSmall Hits Reject   No   No   No   No     Eff <sub>max</sub> (unirr) [%]   99   99   98   99     Eff <sub>max</sub> (irr,centre) [%]   -   98   97   96	Irradiation         Reference         Focussed         Hole (circ.)         Hole (s           Φ [10¹⁵ n <sub>eq</sub> /cm²]         Unirr.         4.0 (max)         1.8         3.3           Sample         CNM 55         CNM 57         FBK 12_02_08         CNM S5-R7           Edge         Regular         Regular         Regular         Slimmed           V <sub>bias</sub> [V]         30         130         58         90         100           Threshold [ke]         3         1.7         2         2         2           ToT @ inj.charge [ke]         10@20         10@20         ~11@20         6@10         ~5@20           SingleSmall Hits Reject         No         No         No         No         Yes           Eff <sub>max</sub> (unirr) [%]         99         99         98         99         95           Eff <sub>max</sub> (irr,centre) [%]         -         98         97         96         94



Unirr.

- Irradiated part (centre) within few % as efficient as unirradiated part
- Significantly lower eff. in ring of irr. part at edge of hole (KIT)
  - Seems not to be due to effectively larger fluence (from position-resolved dosimetry)

### Dependence on FE-I4 chip parameters

#### HitDiscCnfg, PrmpVbnLcc

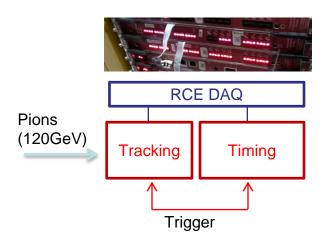
Device + Irrad	Non-Uniform Irradiation	Unirr. Reference	PS Focussed	KIT Hole (circ.)	KIT Hole (slit)		lit)
	$\Phi$ [10 <sup>15</sup> n <sub>eq</sub> /cm <sup>2</sup> ]	Unirr.	4.0 (max)	1.8	3.3		3.6
	Sample	CNM 55	CNM 57	FBK 12_02_08	CNM S5-R7		CNM S3-R5
	Edge	Regular	Regular	Regular	Slim	nmed	Slimmed
MeasSettings	V <sub>bias</sub> [V]	30	130	58	90	100	130
	Threshold [ke]	3	1.7	2	2	2	3
	ToT @ inj.charge [ke]	10@20	10@20	~11@20	6@10	~5@20	~8@20
	SingleSmall Hits Reject	No	No	No	No	Yes	Yes
Results _	Eff <sub>max</sub> (unirr) [%]	99	99	98	99	95	94
	Eff <sub>max</sub> (irr,centre) [%]	1	98	97	96	94	93
	Eff <sub>max</sub> (irr,ring) [%]	-	-	70	93	90	58
					New TB	Prev	Y Vious TB

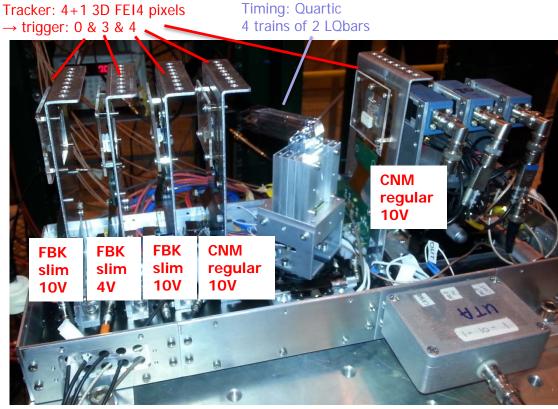
- 3-4% lower efficiency for last two columns (both unirr. and irr. area) due to FE-14 chip setting in previous testbeam (TB)
  - HitDiscCnfg= $2 \rightarrow$  Single small hits (ToT<3) rejected (to avoid time-walk effects, but usually TB analyses take HitDiscCnfg=0)
- Higher efficiency in new testbeam in October 2014 with HitDiscCnfg=0
- No dependence on leakage-current compensation parameter PrmpVbnLcc (0, 100, 200) found

#### **AFP Integration Testbeam**

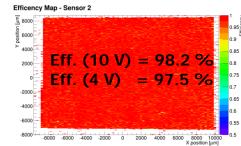
#### November 2014

- AFP system-integration test Tracking + Timing (Quartic+HPTDC)
  - Common trigger
  - Common readout (RCE)  $\rightarrow$  1 data format



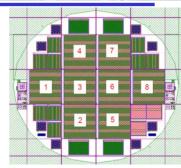


- Integration successful
  - Good performance of tracking and timing detectors
- Simultaneous test of alternative timing systems (Si LGAD and diamond)

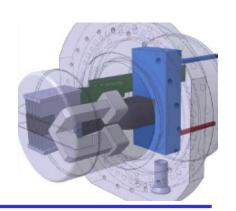


#### **AFP Pixel Module and Station Production**

- AFP run 6682 at CNM finished
  - Lost wafers due to machine malfunctions
  - 5 wafers finished (40 sensors) → UBM at IZM
    - ~9 good sensors after slim-edge dicing (estimated from IV on UBM side)
    - → Yield of good sensors ~23%
    - → Hope to have enough good sensors!
    - 8 needed for 0+2 stage in 2015 (need excellent flip-chipping/assembly yield)
- Flip-chipping (bump-bonding) to FE-I4 to be done at IFAE
- AFP flexible circuit being designed
- Module assembly incl. wire-bonding and QA to be done by IFAE
- Simultaneous production of Roman Pots and Stations
- Timing detectors partially produced, but installation no priority for 0+2 (but desirable to gain experience/study backgrounds)
- → Aim to have pixel modules for first two stations (2x4 3D FE-I4) ready by the end of 2015 (tight!)

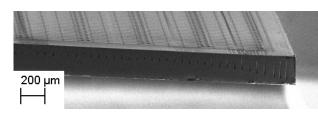






#### Conclusions

- Slim-edge and non-uniformly irradiated 3D AFP sensors studied
  - Insensitive pixel-sensor region highly reduced
    - With guard ring (CNM) insensitive edge down to 143 µm
    - Without guard ring (FBK) even efficient beyond last pixel:
       ~15 µm insensitive edge!
  - High efficiency achievable after non-uniform irradiation at high-lumi fluence (100 fb<sup>-1</sup>)
- → Slim-edge 3D pixel detectors qualified for AFP
- AFP November 2014 integration testbeam successfully finished
- AFP 3D-pixel-module, Roman Pot and station production ongoing
- Aim to have pixel modules for first two stations ready by the end of 2015 (tight!)
- → Second use of 3D silicon sensors in HEP experiment!

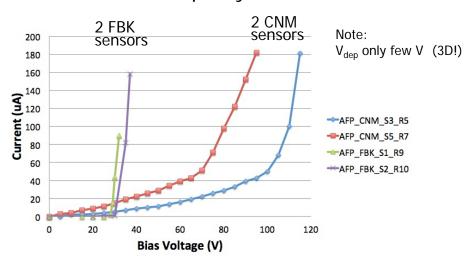


## **BACKUP**

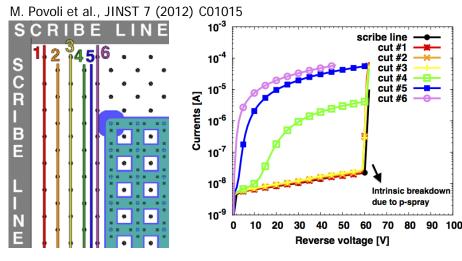


#### **Current and Noise**

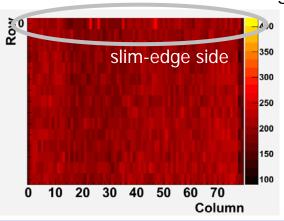
IV of sensors after slimming: normal for sensor-quality class used



Previous study on FBK sensors: IV unaffected up to 100 µm cut line



Noise of CNM device near edge



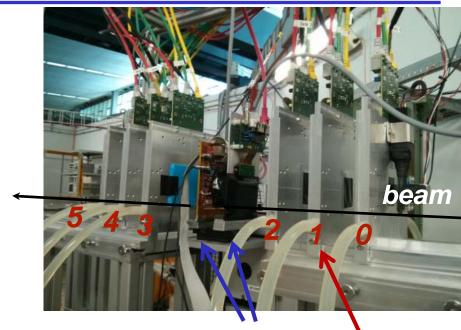
No anomalous current and noise after edge-slimming to 100-180 µm

#### **Test Beam**

- Check performance (hit efficiency) in test beam
  - DESY II 4 or 5 GeV electrons
  - ACONITE telescope (EUDET type)
    - 6 planes of MIMOSA-26:660k Si pixels (18.4 µm pitch)
    - Trigger: 4 scintillators
  - Thanks to AIDA support



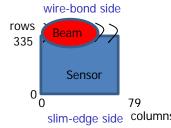
Thanks to all test beam participants, esp. I. Rubinskiy (DESY), D. Pohl (Bonn), O. Korchak (Prague), Sh. Hsu (Washington), A. Micelli (IFAE)

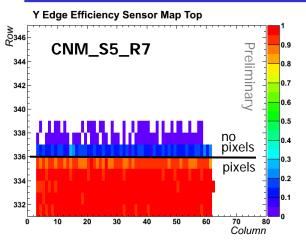


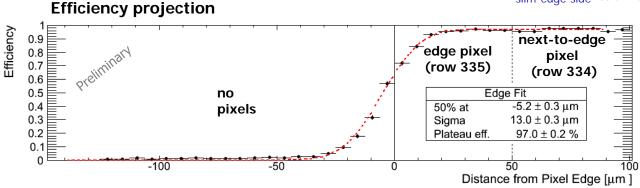


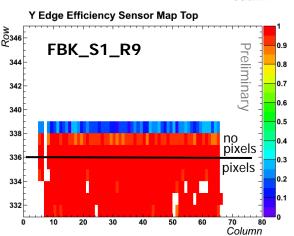
DUTs telescope planes

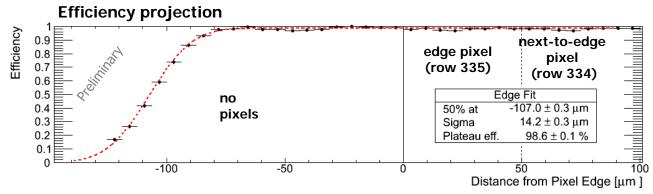
## Regular Unslimmed Edge (Top Side)





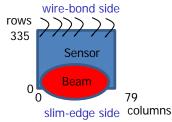


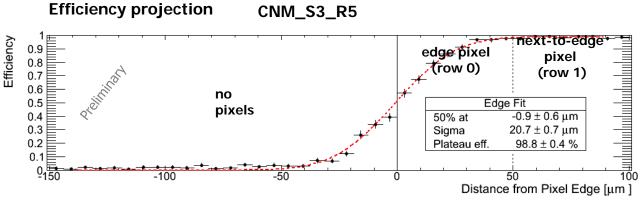


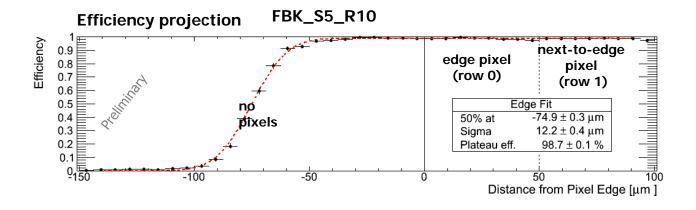


- Efficiency stable up to last pixel
  - Smearing due to beam telescope resolution
  - For FBK even ~100 µm beyond (active edge due to absence of guard ring); a bit noisy/hot pixels → masked

## Slim Edge (Bottom Side) Other devices









#### **Electrical Characteristics**

- Not optimal sensors from beginning (IBL spares)
  - Merged/disconnected bump bonds, partly low V<sub>BD</sub>

#### FBK\_12\_02\_08

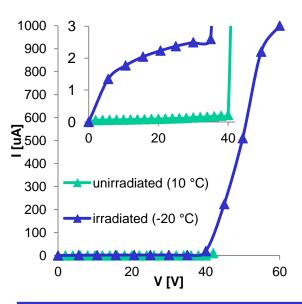
- V<sub>RD</sub> ~ 40 V before and after irrad.
- Able to bias up to 58 V

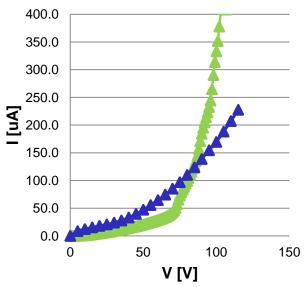
#### CNM\_S5\_R7

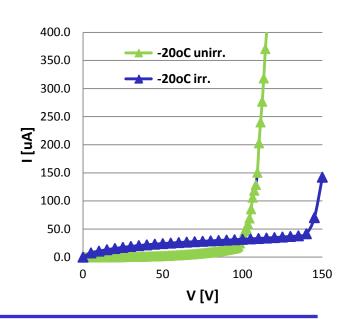
- Soft BD
- Lower I after irr. at high V

#### CNM\_S3\_R5

- Shift of V<sub>BD</sub> to higher V
- Lower I after irr. at high V

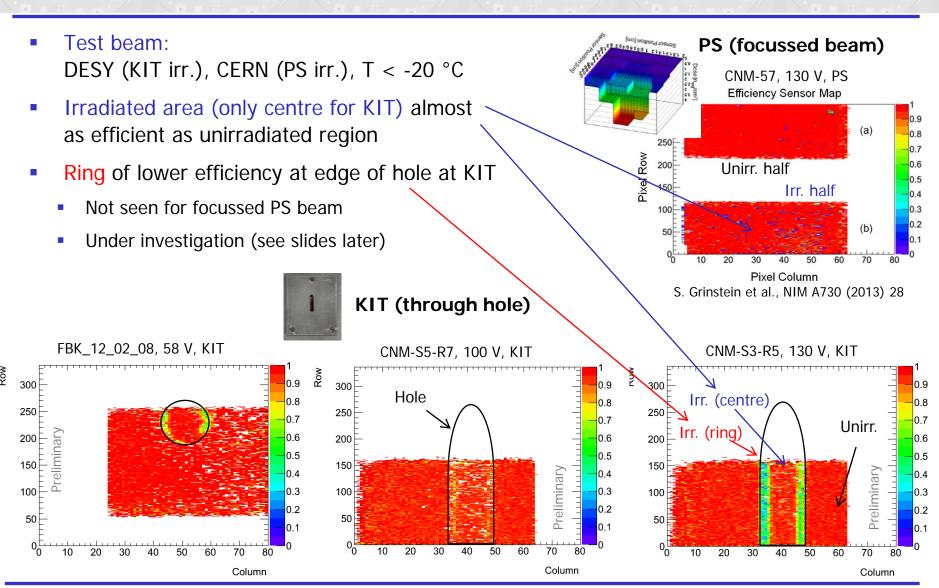






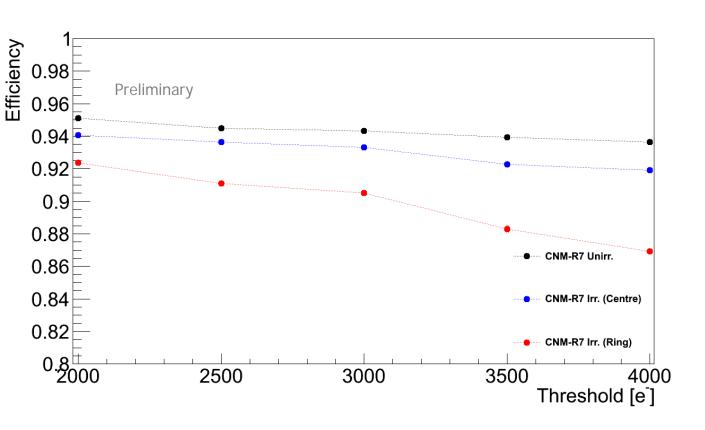


## **Efficiency of Irradiated Devices**



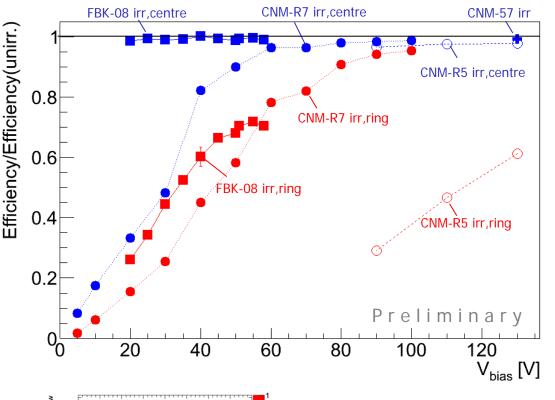
## Efficiency vs. Threshold

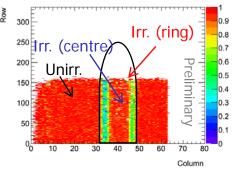
- Improvement of 1% per 1000e reduction of threshold for unirr. and irr. (centre) area
- Even more for higher irradiated ring





## Voltage Dependence of Efficiency/Efficiency(unirr.)



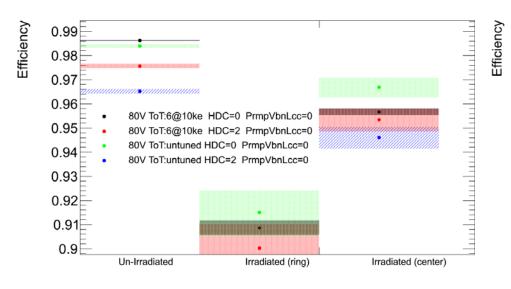


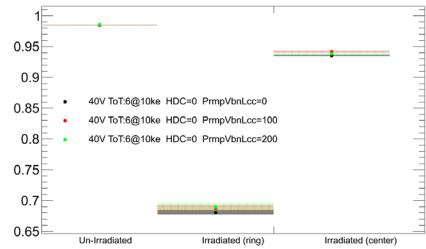
- For better comparison of measurements under different conditions:
   Ratio of efficiency/efficiency(unirr)
- BUT: Curve might change for CNM-R5/7 if measured with HitDiscCnfg =0 (effect on lower eff. is larger)
- Irradiated part (centre)
  - For FBK-08 (1.8x10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup>) plateau reached already below 20V
  - For CNM-R7 (~3.3x10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup>) plateau reached at about 60 V
- Irradiated part (ring)
  - All behave differently
  - FBK seems to saturate at 50 V at ~70%
  - CNM-R7 saturates at 90-100 V at ~90%
  - CNM-R5 much lower, but still steeply increasing at 130 V (60%)

### Dependence on FE-I4 chip parameters

HitDiscCnfg, PrmpVbnLcc

#### CNM-S5-R7 (non-uniformly irradiated, October 2014 CERN TB

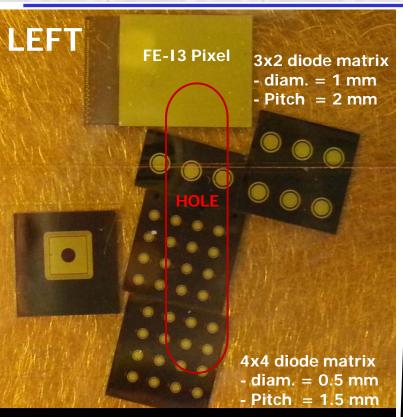


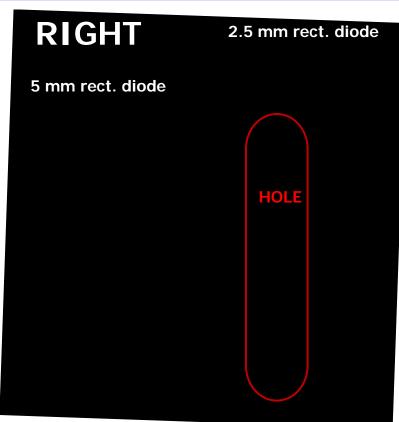


- Efficiency(HDC0) > Efficiency(HDC2)
- For HDC2: Efficiency(ToT tuned) > Efficiency(ToT untuned)

 Efficiencies for different PrmpVbnLcc consistent within uncertainties

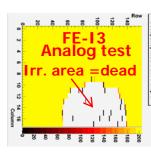
### **Position-Resolved Dosimetry**





Thanks to CNM (G.Pellegrini, M.Baselga) for providing diodes, setup and help!

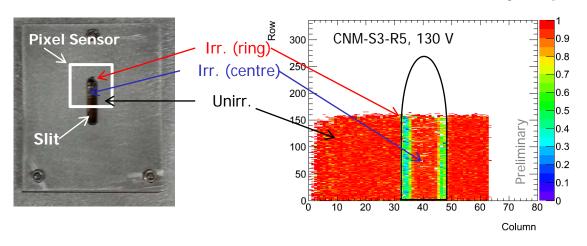
- Multi-device approach (diodes: n-type STFZ, d=300 µm)
- Irradiation under same slit-like Al masks ("left" and "right") as pixel irradiation at KIT
  - Intended: 5-10 x  $10^{13}$   $n_{eq}$ /cm<sup>2</sup> (FE-I3 only specified up to  $<10^{15}$   $n_{eq}$ /cm<sup>2</sup>, reliable plateau for CV/IV)
  - Obtained: 3.4 x 10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup> (FE-I3 dead in irr. area, no CV/IV plateau in irr. area)



## Investigation of Low-Efficiency Ring

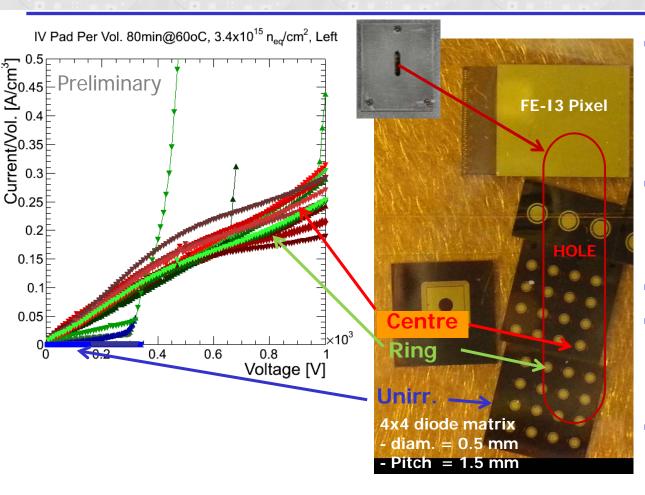
#### 5 mm Al shields:

#### **Pixel-Sensor Efficiency Map**



- Effect of irradiation method with Al shield (possibly higher effective fluence)?
  - Scattering of p at edge of Al shield → loose energy → much more damaging
- Or real effect of abruptly non-uniformly irradiated devices?
  - Sensor effect?
    - Transition region between highly irradiated Si and unirradiated Si
       → huge gradient of defect density and current → maybe leads to lower el. field?
  - Chip effect?

## Position-Resolved Dosimetry from IV



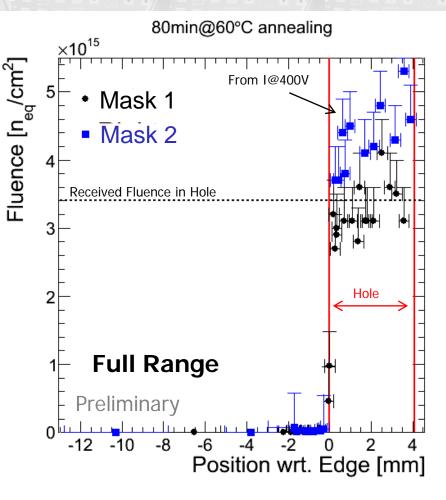
- New irradiation with diode arrays under same slit-like Al masks (left+right) at KIT (3.4 x 10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup>)
- Dosimetry from IV

$$\Delta I(\Phi_{eq}) = \alpha \Phi_{eq} V$$

- Measured at 20 °C
- No real plateau for irradiated diodes, but kink at 400-600 V
   → in the following I/V@400 V for fluence calculation taken
- No significant difference between centre and edge of irr. region

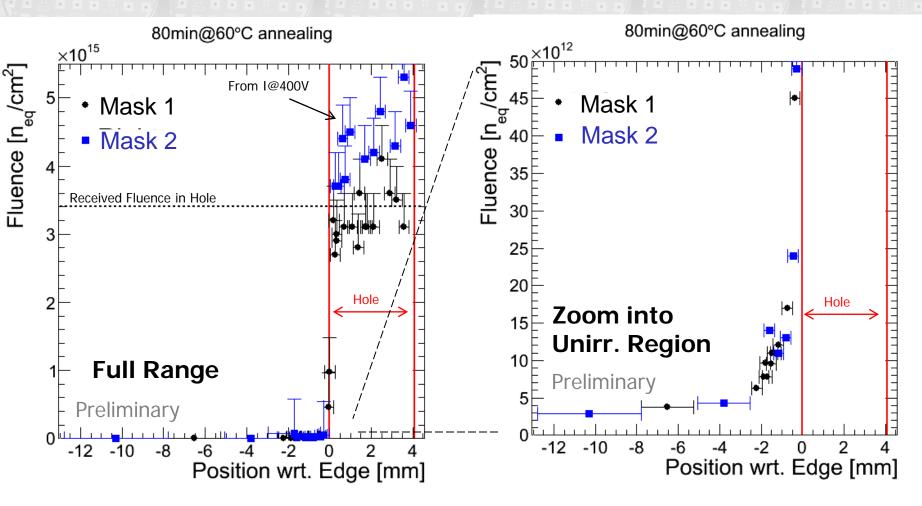
Thanks to CNM (G. Pellegrini, M. Baselga) for providing diodes, setup and help!

## Fluence vs. Position wrt. Edge



- x error bars = extension of diode; upper y error bar to indicate lack of plateau;  $\alpha = 4x10^{17}$  A/cm
- No significant difference between centre and edge of irr. region; consistent with received fluence

## Fluence vs. Position wrt. Edge



- x error bars = extension of diode; upper y error bar to indicate lack of plateau;  $\alpha = 4x10^{17}$  A/cm
- No significant difference between centre and edge of irr. region; consistent with received fluence
- Substantial fluence (~10<sup>12</sup> 10<sup>13</sup> cm<sup>-2</sup>) also under Al mask; higher the closer to the hole